

Docket No. 2312-0866-2 PCT/In

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Kimihiro MATSUSE, et al.

SERIAL NO: 09/530,588

FILED: May 05, 2000

FOR: WIRING STRUCTURE AND ELECTRODE OF SEMICONDUCTOR DEVICE AND METHOD OF MANUFACTURING THE SAME

GAU: 2811

EXAMINER:

INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

Applicant(s) wish to disclose the following information.

REFERENCES

- ☒ The applicant(s) wish to make of record the references, some of which are cited in the attached International Search and Preliminary Examination Report listed on the attached form PTO-1449. Copies of the listed references are attached, where required, as are either statements of relevancy or any readily available English translations of pertinent portions of any non-English language references.
- ☐ A check is attached in the amount required under 37 CFR §1.17(p).

RELATED CASES

- ☐ Attached is a list of applicant's pending application(s) or issued patent(s) which may be related to the present application. A copy of the patent(s) is attached along with PTO 1449.
- ☐ A check is attached in the amount required under 37 CFR §1.17(p).

CERTIFICATION

- ☐ Each item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- ☐ No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

PETITION

- ☐ Applicant(s) hereby request consideration of the attached information. A check is attached in the amount of the Petition fee required under 37 CFR §1.17(i)(1).

DEPOSIT ACCOUNT

- ☒ Please charge any additional fees for the papers being filed herewith and for which no check is enclosed herewith, or credit any overpayment to deposit account number 15-0030. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

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DOCKET NO: 2312-0866-2 PCT

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Group Art Unit: 2811

STATEMENT OF RELEVANCY

Reference AV (JP 64-5015) on Form 1449:

This reference discloses the formation of a tungsten nitride thin film by a vapor phase reaction method of plasma excitation, from a raw material gas containing tungsten hexafluoride gas, nitrogen gas and hydrogen gas.

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